STIC Search Report
EIC 1700

STIC Database Tracking Number: 119444

TO: Mulero Luz L Alejandro
Location: REM 7A19
Art Unit : 1763
April 15, 2004

Case Serial Number: 09/478370

From: Kendra Mellerson
Location: EIC 1700
REM 4B28
Phone: 571-272-2516

Kendra.Mellerson@uspto.gov

Search Notes

No Cases Reported

US 5,792,261

Current session 15/04/2004

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(C) QUESTEL 1994
QUESTEL.ORBIT (TM) 1998                          15/04/04 14*34*31
Last connection: 09/04/04 16*47*18

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Query/Command : FILE PLUSPAT

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QUESTEL      - Time in minutes :    0,65
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Selected file: PLUSPAT

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 Last update of file: 2004/04/07 (YYYY/MM/DD) 2004-14/UP (basic update)

Search statement   1
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Query/Command : US5792261/PN

**** SS 1: Results 1**

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Search statement   2
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Query/Command : PRT FULL NONSTOP LEGALALL

1 / 1 PLUSPAT - ©QUESTEL-ORBIT - image

PN - US5792261 A 19980811 [US5792261]

TI - (A) Plasma process apparatus

PA - (A) TOKYO ELECTRON LTD (JP)

PA0 - Tokyo Electron Limited, Tokyo [JP]

IN - (A) HAMA KIICHI (JP); HATA JIRO (JP); HONGOH TOSHIAKI (JP)

AP - US62410296 19960329 [1996US-0624102]

FD - Cont. of US357423 19941216 [1994US-0357423]
Continuation of: US5525159

PR - US62410296 19960329 [1996US-0624102]
JP34387193 19931217 [1993JP-0343871]
JP7671794 19940323 [1994JP-0076717]
JP7672794 19940323 [1994JP-0076727]
US35742394 19941216 [1994US-0357423]

IC - (A) C23C-016/00

EC - C23C-016/44A4
C23C-016/455
C23C-016/50
C23C-016/505

ICO - M23C-016/44E20
T01J-237/32C

PCL - ORIGINAL (O) : 118723000I; CROSS-REFERENCE (X) : 118723000R
156345260 156345290 156345370 156345480

DT - Basic

CT - US4563367; US5167717; US5280154; US5326404; US5413684; US5494522; US5542559; US5580385

STG - (A) United States patent

AB - A plasma CVD apparatus for forming a silicon film on an LCD substrate includes a container which is divided into process and upper chambers by a quartz partition plate. A work table on which the substrate is mounted is arranged in the process chamber and a lower electrode to which a high frequency potential is applied is arranged in the work table. First lower and second upper supply heads are arranged between the partition plate and the work table in the process chamber. SiH4 and H2 gas and He gases are supplied through the first and second supply heads. He gas is transformed into plasma while SiH4 and H2 gas is excited and decomposed by the plasma thus formed. Two coils are arranged in the upper chamber and high frequency voltages are applied to the coils to generate electromagnetic field to induce the transforming of He gas into plasma. High frequency voltages applied to the coils are the same in phase and directions of current flowing through adjacent portions of the coils are the same.

1 / 1 LGST - ©EPO

PN - US5792261 A 19980811 [US5792261]

AP - US62410296 19960329 [1996US-0624102]

ACT - 20000829 US/RF-A

REISSUE APPLICATION FILED
EFFECTIVE DATE: 20000106

UP - 2003-22

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1 / 1 CRXX - ©CLAIMS/RRX

PN - 5,792,261 A 19980811 [US5792261]

PA - Tokyo Electron Ltd JP

ACT - 20000106 REISSUE REQUESTED
Issue Date of O.G.: 20000829
Reissue Request Number: 09/478370
Examination Group responsible for Reissue process: 1763

Query/Command : FILE INPADOC

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PLUSPAT       - Time in minutes :   0,56
The cost estimation below is based on Questel's
standard price list
                              Estimated cost :    1.35 USD
Records displayed and billed   :      1
                              Estimated cost :    1.32 USD
Cost estimated for the last database search :    2.67 USD
Estimated total session cost                :    3.32 USD

LGST          - Time in minutes :   0,09
The cost estimation below is based on Questel's
standard price list
                              Estimated cost :    0.11 USD
Records displayed and billed   :      1
                              Estimated cost :    0.60 USD
Legal-Status informations      :      1
                              Estimated cost :    0.50 USD
Cost estimated for the last database search :    1.21 USD
Estimated total session cost                :    4.53 USD

CRXX          - Time in minutes :   0,06
The cost estimation below is based on Questel's
standard price list
                              Estimated cost :    0.10 USD
Records displayed and billed   :      1
                              Estimated cost :    5.50 USD
Legal-Status informations      :      1
                              Estimated cost :    0.50 USD
Cost estimated for the last database search :    6.10 USD
Estimated total session cost                :   10.63 USD

LITA          - Time in minutes :   0,01
The cost estimation below is based on Questel's
standard price list
                              Estimated cost :    0.02 USD
Cost estimated for the last database search :    0.02 USD
Estimated total session cost                :   10.65 USD

Selected file: INPADOC

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Search statement 1

Query/Command : FAM US5792261/PN

1 Patent Groups

** SS 1: Results 7

Search statement 2

Query/Command : FAMSTATE NONSTOP

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1 / 7 INPADOC - ©INPADOC

PN - JP 3150027 B2 20010326 [JP3150027]
AP - JP 76717/94-A 19940323 [1994JP-0076717]
PR - JP 76717/94-A 19940323 [1994JP-0076717]
JP 343871/93-A 19931217 [1993JP-0343871]
IC - H01L-021/205; C23C-016/505; G02F-001/1368; H01L-021/31; H05H-001/46

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2 / 7 INPADOC - ©INPADOC

PN - JP 3422583 B2 20030630 [JP3422583]
AP - JP 329329/94-A 19941201 [1994JP-0329329]
PR - JP 329329/94-A 19941201 [1994JP-0329329]
JP 76727/94-A 19940323 [1994JP-0076727]
IC - H01L-021/205; C23C-016/44; H01L-021/3065; H01L-021/31; H05H-001/46

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3 / 7 INPADOC - ©INPADOC

PN - JP 7226383 A2 19950822 [JP07226383]
TI - PLASMA GENERATING DEVICE AND PLASMA TREATMENT DEVICE USING THIS PLASMA GENERATING DEVICE
IN - HAMA KIICHI; HATA JIRO
PA - TOKYO ELECTRON LTD
AP - JP 76717/94-A 19940323 [1994JP-0076717]
PR - JP 76717/94-A 19940323 [1994JP-0076717]
JP 343871/93-A 19931217 [1993JP-0343871]
IC - H01L-021/205; C23C-016/50; H01L-021/31

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4 / 7 INPADOC - ©INPADOC

PN - JP 7312348 A2 19951128 [JP07312348]
TI - METHOD AND APPARATUS FOR TREATMENT
IN - HATA JIRO; HAMA KIICHI; HONGO TOSHIAKI
PA - TOKYO ELECTRON LTD
AP - JP 329329/94-A 19941201 [1994JP-0329329]
PR - JP 329329/94-A 19941201 [1994JP-0329329]
JP 76727/94-A 19940323 [1994JP-0076727]
IC - H01L-021/205; H01L-021/31; H05H-001/46

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5 / 7 INPADOC - ©INPADOC

PN - KR 272189 B1 20001201 [KR-272189]
TI - PLASMA TREATMENT APPATATUS
IN - HAMA KIICHI [JP]; HATA JIRO [JP]; HONGO DOSHIAKI [JP]
PA - TOKYO ELECTRON LTD [JP]
AP - KR 9434797/94-A 19941217 [1994KR-0034797]
PR - JP 343871/93-A 19931217 [1993JP-0343871]
JP 76717/94-A 19940323 [1994JP-0076717]
JP 76727/94-A 19940323 [1994JP-0076727]
IC - H01L-021/302

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6 / 7 INPADOC - ©INPADOC

PN - US 5525159 A 19960611 [US5525159]
TI - PLASMA PROCESS APPARATUS
IN - HAMA KIICHI [JP]; HATA JIRO [JP]; HONGOH TOSHIAKI [JP]
PA - TOKYO ELECTRON LTD [JP]
AP - US 357423/94-A 19941216 [1994US-0357423]
PR - JP 343871/93-A 19931217 [1993JP-0343871]
JP 76717/94-A 19940323 [1994JP-0076717]
JP 76727/94-A 19940323 [1994JP-0076727]
IC - C23C-016/00

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1 / 1 LEGALI - ©EPO

PN - US5525159 A 19960611 [US5525159]
AP - US35742394 19941216 [1994US-0357423]
ACTE - 19941216 US/AS02-A
ASSIGNMENT OF ASSIGNOR'S INTEREST
OWNER: TOKYO ELECTRON LIMITED 3-6 AKASAKA 5-CHOME, MINATO; EFFECTIVE DATE: 19941208

19941216 US/AS02-A
ASSIGNMENT OF ASSIGNOR'S INTEREST
OWNER: HAMA, KIICHI,; EFFECTIVE DATE: 19941208

19941216 US/AS02-A
ASSIGNMENT OF ASSIGNOR'S INTEREST
OWNER: HATA, JIRO; EFFECTIVE DATE: 19941208

19941216 US/AS02-A
ASSIGNMENT OF ASSIGNOR'S INTEREST
OWNER: HONGOH, TOSHIAKI; EFFECTIVE DATE: 19941208

UP - 2003-22

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7 / 7 INPADOC - ©INPADOC

PN - US 5792261 A 19980811 [US5792261]

TI - PLASMA PROCESS APPARATUS

IN - HAMA KIICHI [JP]; HATA JIRO [JP]; HONGOH TOSHIAKI [JP]

PA - TOKYO ELECTRON LTD [JP]

AP - US 624102/96-A 19960329 [1996US-0624102]

PR - US 624102/96-A 19960329 [1996US-0624102]
JP 343871/93-A 19931217 [1993JP-0343871]
JP 76717/94-A 19940323 [1994JP-0076717]
JP 76727/94-A 19940323 [1994JP-0076727]
US 357423/94-A1 19941216 [1994US-0357423]

IC - C23C-016/00

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1 / 1 LEGALI - ©EPO

PN - US5792261 A 19980811 [US5792261]

AP - US62410296 19960329 [1996US-0624102]

ACTE - 20000829 US/RF-A
REISSUE APPLICATION FILED
EFFECTIVE DATE: 20000106

UP - 2003-22

PATNO IS 5792261

DATE: APRIL 15, 2004
LIBRARY: PATENT
FILE: ALL

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PATNO IS 5792261

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LEVEL 1... 1

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For further explanation, press the H key (for HELP) and then the ENTER key.

LEVEL 1 - 1 PATENT

1. 5792261 , August 11, 1998 , Plasma process apparatus, Hama, Kiichi, Chino, JP; Hata, Jiro, Yamanashi-ken, JP; Hongoh, Toshiaki, Yamanashi-ken, JP, 624102 (08), Tokyo Electron Limited, Tokyo, JP

CORE TERMS: substrate, chamber, coil, gas, plasma, pipe, film, sub, supplied, electrode ...

LEVEL 1 - 1 OF 1 PATENT

UNITED STATES PATENT AND TRADEMARK OFFICE GRANTED PATENT

5792261

<=1> GET 1st DRAWING SHEET OF 10

August 11, 1998

Plasma process apparatus

REISSUE: Reissue Application filed Jan. 6, 2000 (O.G. Aug. 29, 2000) Ex. Gp.: 1763; Re. S.N. 09/478,370, (O.G. August 29, 2000)

APPL-NO: 624102 (08)

FILED-DATE: March 29, 1996

GRANTED-DATE: August 11, 1998

CORE TERMS: substrate, chamber, coil, gas, plasma, pipe, film, sub, supplied, electrode ...

5792261 OR 5,792,261

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